Laser heating of pinch plasma for EUV emission: Determination of plasma parameters and spectrally resolved tomography

A laser heated gas discharge plasma source is developed, and influence of the laser pulse on plasma properties and emission characteristics is analyzed. The source consists of a hollow cathode triggered gas discharge EUV source with a custom precision trigger and a pulsed CO_2 TEA laser at 10.6 μ m for additional heating of the magnetically self-compressed plasma pinch. An increase of emitted EUV power and pulse duration is found.

The change in the transient plasma temperature and density is retrieved by a composition sensitive analysis method from measured spectra. The method is based on plasma emission modelling using the CHIANTY atomic data base and applying a constrained and regularized linear least squares algorithm. The 3-dimensional emitting volume is determined for certain emission lines by a model based tomographic reconstruction method.

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